

Form PTO-1449

U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEATTY. SCKET NO.  
M122-1098PRIORITY SERIAL NO.  
08/696,243LIST OF ART CITED BY APPLICANT  
(Use several sheets if necessary)APPLICANT  
Klaus F. SchuegrafPRIORITY FILING DATE  
08/13/96PRIORITY GROUP  
2813

## U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
EK	AA	5,763,018	6/1998	Sato	438	790	
EK	AB	5,710,079	1/1998	Sukharev	438	778	
	AC	5,238,671	8/1993	Matson et al.	423	397	
	AD	5,610,105	3/1997	Vines et al.	437	238	
	AE	5,472,913	12/1995	Havemann et al.	437	238	
	AF	5,470,800	11/1995	Muroyama	437	238	
	AG	5,462,899	10/1995	Ikeda	437	238	
	AH	5,580,822	12/1992	Hayakawa et al.	437	187	
	AI	5,420,075	5/1995	Homma et al.	437	195	
EK	AJ	5,360,646	11/1994	Morita	427	574	

## FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL	6349747	12/1994	Japan				
	AM							
	AN							
	AO							
	AP							

## OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

EK	AR		IslamRaja, et al., "Two Precursor Model For Low-Pressure Chemical Vapor Deposition Of Silicon Dioxide From Tetrethylorthosilicate", J. Vac. Sci. Technol. B, Vol. 11, No. 3, May/Jun 1993, pp. 720-726.
EK	AS		Crowell, John E. et al., "The Chemical Vapor Deposition Of SiO <sub>2</sub> From TEOS", Journal of Electron Spectroscopy And Related Phenomena, 54/55 (1990) pp. 1097-1104.
EK	AT		Hauptfear, E.A. et al., "Kinetics of SiO <sub>2</sub> Deposition From Tetraethylorthosilicate", Electrochem. Soc. Vol. 141, No. 7, July 1994, pp. 1943-1950.

EXAMINER

*EK/Kelvin*

DATE CONSIDERED

*6/14/20*

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1098		PRIORITY SERIAL NO. 08/696,243	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Klaus F. Schuegraf			
				PRIORITY FILING DATE 08/13/96		PRIORITY GROUP 2813	
U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
CK	AA	5,182,221	1/1993	Sato	437	67	
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	AL						
	AM						
	AN						
	AO						
	AP						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
CK	AR		Wolf, Stanley, "Silicon Processing for the VLSI Era", Vol. 1, pp. 166-171				
CK	AS		"Hawley's Condensed Chemical Dictionary", 12th Ed., 1993, pg. 500				
	AT						
EXAMINER			DATE CONSIDERED				
Erik Koster			6/14/00				
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							